Supplemental Material

Design of First-Order 121.6 nm Minus Filters

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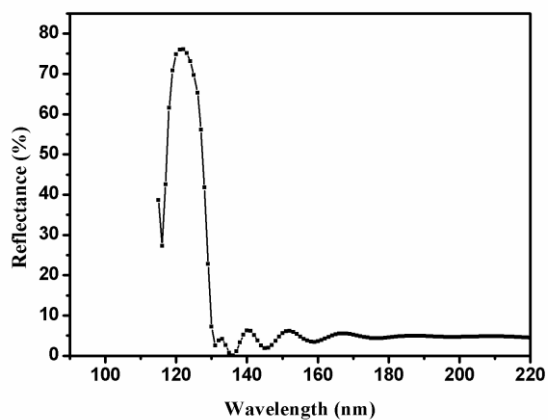Corresponding author email: wangxiaodong@ciomp.ac.cn

Figure S1. Theoretical reflectance curve of periodic multilayer of sub/(0.7H0.6L0.7H)^11/air, and the incident angle is 10°.
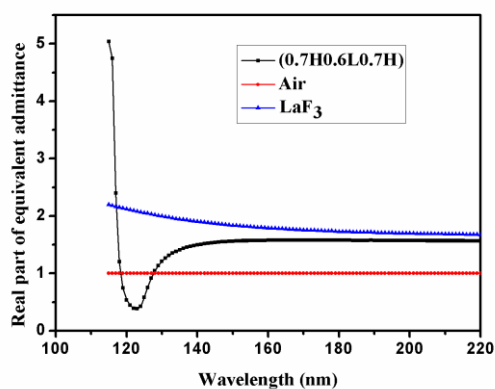

Figure S2. Real part of equivalent admittance of periodic multilayer (0.7H0.6L0.7H), and the incidence angle is 10°.
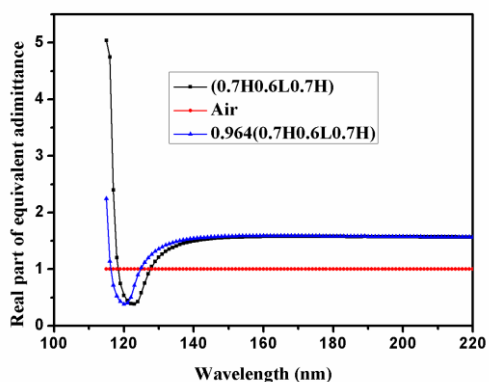
Figure S3. Real pat of equivalent admittance of multilayer 0.964(0.7H0.6L0.7H), the incidence angle is 10°.
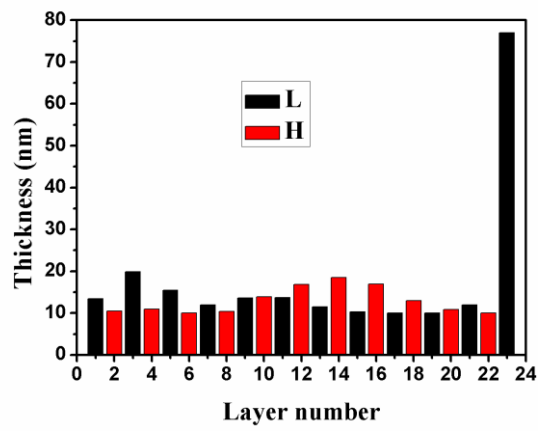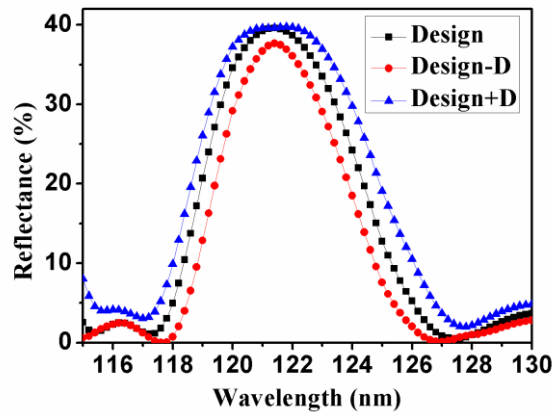

Figure S4. Final design result of 121.6 nm minus filter.

Figure S5. Error analysis result of final design.